L	Hits	Search Text	DB	Time stamp
Number	· · · · · · · · · · · · · · · · · · ·			
1	372378	<pre>(mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:49
2	99250	<pre>((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:56
3	380140	"3" and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:54
4	17743	<pre>(((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:56
	8	(support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))		
5	611	<pre>((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20
6	50	(((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1)) and (substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20

	1		T	0004/00/00
7	1	((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	07:59
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		•
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		*		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		(((mask\$4 or pattern\$4) same (negative	,	
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
ŀ		rotat\$4)) same ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4)))		
	177		ticnam.	2004/01/20
8	17	((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
1		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:08
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
į		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
-		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4))) and lithography		
11	4	((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
**		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:07
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	""
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
1		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
1		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
	1	and ((workpiece\$1 or substrate\$1) same		
	1	(stage\$4 and mov\$4 and rotat\$4))) and		
	1			
	1	((mask\$4 or pattern\$4) same (negative		
1		with (photosensitive or layer\$1 or		
1		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
		rotat\$4))) and lithography) and		
1		430/\$.ccls.		

1 (((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((inx\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or drop\$4 or droplet\$4)) and ((mask\$4 or pattern\$4) same (mask\$4 or pattern\$4) same (support\$4) and (mask\$4 or pattern\$4) same (stage\$4 and mov\$4 and rotat\$4)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((inx\$4] or liquid\$1 or fluid\$1) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((inx\$1 or liquid\$1 or fluid\$1) and ((mask\$4 or pattern\$4) same (support\$4 or lept\$4 or lep					
((mask34 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$41)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$41)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$41)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$11)) and ((workpiece\$1 or substrate\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) same (support\$4 or align\$4 or mov\$4 or rotat\$41)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$41)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$41)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4])) and (mask\$4	12	1	(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	
(photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or drop\$4 exp\$1] and ((mas\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and (substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and (ideorkpiece\$1 or substrate\$1) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((mas\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and (in\$6 or rotat\$4)) and (in\$6 or rotat\$4)) and (in\$6 or rotat\$4)) and ((mas\$4 or pattern\$4) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((mas\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mas\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and (same (negative with (photosensitive or layer\$1 or resist\$1) an			1		
(support% or align% 4 or stage% 4 or mov% 4 or rotat% 4)) and (sink% 1 or liquid\$1 or fluid\$1) same (deposit% 4 or eject% 4 or jets% 4 or drop% 4 or drop% 4 or drop% 1 or drop% 1 or drop% 1 or drop% 4 or resist\$1)) and ((mas% 4 or pattern% 4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mas% 4 or pattern% 4) and (mas% 4 or pattern% 4) same (support% 4 or align% 4 or stage% 4 or mov% 4 or rotat% 4)) and (imas% 4 or pattern% 4) same (support% 4 or align% 4 or stage% 4 or mov% 4 or rotat% 4)) and (imas% 4 or pattern% 4) same (support% 4 or align% 4 or stage% 4 or mov% 4 or rotat% 4)) and (imas% 4 or pattern% 4) same (photosensitive or layer\$1 or resist\$1) and ((mas% 4 or pattern% 4) same (mas% 4 or pattern% 4) and (mas% 4 or pattern% 4) same (mas% 4 or pattern% 4) and (mas% 4 or pattern%					
or rotats4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jett\$4 or drop\$4 or drop\$1 and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and (vorkpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)) and (ink\$1) and lithography) and (27/\$, ccls. 13 (((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and ((mosk\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or pattern\$4) same (support\$4 or align\$4 or eject\$4 or jett\$4 or drop\$4 or substrate\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mosk\$4 or pattern\$4) same (photosensitive or layer\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) or substrate\$1) same (support\$4 or aliqn\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((mask\$4 or pattern\$4) or substrate\$1) same (support\$4 or aliqn\$4 or substrate\$1) same (support\$4 or aptern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1) and (stage\$4 and mov\$4 and rotat\$4])) and (stage\$4				-8-	,
fluid\$1) same (deposit\$4 or eject\$4 or jeet\$4 or drop\$4 or droplet\$4) and ((mask\$4 or pattern\$4) same (photosenstive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)) and lithography) and 427/\$.ccls. 13					
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and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and (27/\$.ccls. 13			((mask\$4 or pattern\$4) same		
(stage\$4 and mov\$4 and rotat\$4)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and i(hography) and 27/\$.col. 13					
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with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1)) and (ithography) and 427/\$.ccls. 13 (((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4)) and ((mask\$4 or or tlayer\$1 or resist\$1)) and ((mask\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((imask\$4 or pattern\$4)) and ((mask\$4 or pattern\$4))) and ((mask\$4 or pattern\$4)) and ((mask\$4 or pattern\$4))) and ((mask\$4 or pattern\$4)) and (mask\$4 or pattern\$					
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rotat\$4)) and lithography) and 427/\$.ccls. {(((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or drop\$1 same (stage\$4 and mov\$4 and rotat\$4)) and ((mask\$4 or pattern\$4)) and ((mask\$4 or pattern\$4)) and ((mask\$4 or pattern\$4)) and ((mask\$4 or pattern\$4)) and (mask\$4 or pattern\$4)) and (morkpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((morkpiece\$1 or substrate\$1)) and ((morkpiece\$1) same (stage\$4) and mov\$4 and rotat\$4)) and (inthography) not ((((((((mask\$4 or pattern\$4) ame (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4)) and (mask\$4 or pattern\$4)) and ((mask\$4 or pattern\$4))) and ((mask\$4 or pattern\$4)) and (mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and (mask\$4 or pattern\$4) same (negative with (photosensitive or la]				
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<pre>jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and</pre>					
<pre>((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and</pre>					
<pre>(photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and</pre>					
<pre>(stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and</pre>			<pre>(photosensitive or layer\$1 or resist\$1))</pre>		
<pre>((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and</pre>					
<pre>with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and</pre>					
resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and					
rotat\$4))) and lithography) and			resist\$1))) and ((workpiece\$1 or	l .	

21	31	(((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
	İ	(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:40
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
ĺ		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) not		
		((((((mask\$4 or pattern\$4) and		
	İ	(photosensitive or layer\$1 or resist\$1)		
		and (workpiece\$1 or substrate\$1)) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		<u>.</u>
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		·
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
	1	((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
i	1	rotat\$4)))) and 347/\$.ccls.	I	

20	530	(////magk\$4 or mattern\$4) and	USPAT;	2004/01/20
22	530	<pre>((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1)</pre>	US-PGPUB;	08:40
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	00.40
		((mask\$4 or pattern\$4) same	DERWENT	
			DEKWENT	
		<pre>(photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same</pre>		
		1		
		(support\$4 or align\$4 or stage\$4 or mov\$4		}
		or rotat\$4))) and ((ink\$1 or liquid\$1 or	İ	
		fluid\$1) same (deposit\$4 or eject\$4 or	1	į
		jet\$4 or drop\$4 or droplet\$4))) and		
	Ï	((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
İ		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) not		
		((((((mask\$4 or pattern\$4) and		
	<u> </u>	(photosensitive or layer\$1 or resist\$1)		
	1	and (workpiece\$1 or substrate\$1)) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or	1	
	1	fluid\$1) same (deposit\$4 or eject\$4 or		
		jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		
	ļ	rotat\$4)))) not ((((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
	1	or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
	ļ	substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) not (((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or	1	
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
1		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) and ((mask\$4 or pattern\$4)		
		same (negative with (photosensitive or		
		layer\$1 or resist\$1))) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4)))) and 347/\$.ccls.)		
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(photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and EFO_JFOrD DERMENT (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((lnx\$31 or liquid\$1 or fluid\$1 or fluid\$4))) and ((lnx\$31 or liquid\$1 or fluid\$1 or fluid\$2 or expected or design\$4 or droplet\$4 or stage\$4 or drop\$4 or pattern\$4) and ((photosensitive or layer\$1 or resist\$1)) and ((max\$4 or pattern\$4) and (inax\$4 or patte	23	87	((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
and (workpieces) or substrate(1) and (mas%4 or patterns(4) same (supports(4) or layers(1) or resist(1)) and (workpieces) or substrate(3) same (supports(4) or aligns(4) or stage(5) or mov(5) or rotat(5(4)) and ((ink(5) or layers(1) or rotat(5(4)) and ((ink(5) or layers(1))) and (workpieces(1) or substrate(5(1)) and (workpieces(1) or substrate(5(1)) and ((workpieces(1) or substrate(5(1))) and ((workpieces(1) or substrate(5(1))) and ((ink(5)) or rotat(5(4))) and (ink(5(4)) or rotat(5(43) ,		1	· · ·
((mask% or patterns%) same (supports% or aligns% or stages% or movs% or rotats%))) and ((ink%l or liquids) or fluid%)) and ((ink%l or liquids) or jets% or dropp% or droplets%))) and ((mask% or patterns%) same (supports% or aligns% or stages% or jets% or dropp% or droplets%))) and ((mask% or patterns%) same (photosensitive or layers% or resist%)) and (workpieces% or substrate%)) and ((j(((imask% or patterns%)) same ((i(((imask% or patterns%)) same ((photosensitive or layers% or resist%)) and ((workpiece%) or substrate%)) and ((mask% or patterns%) same (supports% or aligns% or stages% or movs% or rotats%))) and ((ink%l or liquids) or fluid%)) same (deposit% or sject% or juts% or dops% or dopterns%) same ((mask% or patterns%) same (supports% or aligns% or sject% or juts% or dops% or doplets%))) and ((mask% or patterns%) same (supports% or daterns%) same (supports% or aligns% or sject% or juts% or dops% or doplets%))) and ((workpieces%) or substrate%)) same (photosensitive or layers%) or patterns%) and ((ink%leces%) or substrates%) same (stages% and movs% and rotats%))) and ((inks%) or patterns%) or resist%))) and ((inks%) or patterns%) same (stages% and movs% and rotats%))) and ((inks%) or patterns%) same (photosensitive or layers%) or resist%))) and ((inks%) or patterns%) same (photosensitive or layers%) or resist%))) and ((inks%) or patterns%) same (photosensitive or layers%) or resist%)) and ((inks%) or patterns%) same (supports% or aligns% or stages% or movs% or ortats%))) or substrates%) same (stages% or dops% or doplets%))) and ((inks%) or patterns%) same (spotosensitive or layers%) or resist%)) and ((inks%) or patterns%) same (spotosensitive or layers%) or substrates%) same (stages% or drops% or doplets%))) and ((inks%) or patterns%) same (spotosensitive or layers%) or resist%)) and ((inks%) or patterns%) same (spotosensitive or layers%) or substrates%) same (stages% and movs% and rotats%)) and ((inks%) or patterns%) same (spotosensitive or layers%) or substrates%) same (stages% and movs% and rotats%)) and				· ·	00.40
(photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and (stage\$4 and mov\$4 and rotat\$4)) not (((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) and ((mask\$4 or pattern\$4) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jor\$4 or drop\$6 or droplet\$91)) and ((photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((((mask\$4 or pattern\$4))) mot ((((((mask\$4 or pattern\$4)))) mot ((((((mask\$4 or pattern\$4)))) mot ((((((mask\$4 or substrate\$1)))) and (((((mask\$4 or substrate\$1))) and ((((((mask\$4 or substrate\$1)))) and (((((((((((((((((((((((((((((((((((
and ((workpiece\$) or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4!)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4!)) and ((max\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1]) and (workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4!)) and ((intomensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) and ((max\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) and ((morkpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4!)) and ((int\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4!)) and ((max\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1]) and (workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4!)) and ((int\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4!)) and ((max\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1]) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4!)) and ((max\$4 or pattern\$4) same (negative workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4!)) not (((((max\$4 or pattern\$4) and ((horkpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4!)) inot ((((((max\$4 or pattern\$4) and ((borkpiece\$1 or substrate\$1)) and ((workpiece\$1 or substrate\$1)) and ((workpiece\$1 or substrate\$1)) and ((workpiece\$1 or substrate\$1)) and ((workpiece\$1 or substrate\$1)) ame ((portpiece\$1 or substrate\$1)) and ((workpiece\$1 or substrate\$1)) and ((workpiece\$1 or substrate\$1)) and ((workpiece\$1 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and (max\$4 or pattern\$4) same (peposit\$4 or eject\$4 or or layer\$1 or resist\$1]) and ((max\$4 or or layer\$1 or resist\$1]) and (wor			((mask\$4 or pattern\$4) same	DERWENT	
and ((workpiece\$) or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4!)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4!)) and ((max\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4]) not ((internative pattern\$4) same (stage\$4 and mov\$4 and rotat\$4]) and ((max\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) and ((morkpiece\$1 or substrate\$1) same (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4!) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4!) and ((max\$4\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1] same (stage\$4 and mov\$4 and rotat\$4!)) and ((max\$6\$ or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4!)) and ((max\$6\$ or pattern\$4) same (negative variat\$21)) and ((ink\$6\$ or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4!)) not (((inkas\$6 or pattern\$4) and (photosensitive or layer\$1 or resist\$1)) and ((max\$6 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and ((inkas\$6 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 or droplet\$4!)) and ((ink\$6 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and ((workpiece\$1 or substrate\$1) same (stage\$4 or drop\$4 or droplet\$4!)) and ((ink\$6 or pattern\$4) same (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) same (stage\$4 or drop\$4 or droplet\$4!)) and (max\$6 or pattern\$4) same (photosensitive or layer\$1 or resist\$1] and (workpiece\$1 or substrate\$1) same (stage\$4 or drop\$4 or droplet\$4!)) and (max\$6 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) same (stage			(photosensitive or laver\$1 or resist\$1))		
(supports4 or aligns4 or stage84 or mov84 or rotat84)) and ((ink81 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or deposit\$0 or depote\$4)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or rosist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$41)) not ((((((imask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1)) and (workpiece\$1 or substrate\$1) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and ((inak\$4 or pattern\$4) and ((inak\$4 or pattern\$4) and ((inak\$4 or pattern\$4) and ((inak\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same ((support\$4 or align\$4 or eject\$4 or jet\$4 or drop\$4 or drop\$4 or potat\$4)) and ((inak\$4 or jet\$4 or jet\$4 or drop\$4 or drop\$4 same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same ((stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((morkpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not resist\$1)) and ((workpiece\$1 or substrate\$1) or resist\$1)) and ((inak\$4 or pattern\$4) and (inak\$4 or pattern\$4) and (inak\$6 or layer\$1 or resist\$1) and (inak\$6 or layer\$1 or resist\$1) and (inak\$6 or layer\$1 or layer\$1 or layer\$1 or l					
or rotats[4]) and ((ink\$] or liquids] or fluids]) same (deposits] or jets4 or drops4 or droplets[4]) and ((maxk\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotats[4]) not ((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1) and (photosensitive or layer\$1 or resist\$1) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1]) and ((workpiece\$1 or substrate\$1]) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotats[4]) and ((ink\$1 or liquids] or fluids]) same (deposit\$4 or sign\$4 or eject\$4 or jet\$4 or jet\$4 or drop\$4 or droplet\$4)) and ((maxk\$4 or pattern\$4) same (rotage\$4 and mov\$4 and rotat\$4)) and ((maxk\$4 or pattern\$4) same (repative with (photosensitive or layer\$1 or resist\$1)) and ((maxk\$4 or pattern\$4) same (repative with (photosensitive or layer\$1 or resist\$1)) and ((maxk\$4 or pattern\$4) same (rotage\$4 and mov\$4 and rotat\$4))) not ((((((mask\$4 or pattern\$4) same (rotage\$4 and mov\$4 and rotat\$4))) not (((((((mask\$4 or pattern\$4) same (stage\$4 and mov\$4 and rotat\$4))) not (((((((mask\$4 or pattern\$4) same (stage\$4 and mov\$4 and rotat\$4))) not (((((((mask\$4 or pattern\$4) same (stage\$4 or mov\$4 or resist\$1)) and (morkpiece\$1 or substrate\$1) same (stage\$4 or mov\$4 or resist\$1)) and (morkpiece\$1 or substrate\$1) same (stage\$4 or mov\$4 or resist\$1)) and ((morkpiece\$1 or substrate\$1) same (stage\$4 or mov\$4 or drop\$4 or resist\$1)) and (((morkpiece\$1 or substrate\$1)) and ((morkpiece\$1 or substrate\$1)) and ((morkpiece\$1 or substrate\$1)) and ((morkpiece\$1 or substrate\$1)) and ((morkpiece\$1 or pattern\$4)) and (morkpiece\$1 or pattern\$4) same (deposit\$4 or eject\$4 or drop\$4 or dr	i				
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or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and 347/\$.ccls.)) and			resist\$1)) and ((workpiece\$1 or		
or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and 347/\$.ccls.)) and			substrate\$1) same (support\$4 or align\$4		
<pre>((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and</pre>					1
<pre>(deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and</pre>					
or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and		· ·			
pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and)
layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and					
or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and			pattern\$4) same (photosensitive or		
or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and				,	į l
and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and			1 4		
same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and					
layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and					
or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and				İ	
and rotat\$4)))) and 347/\$.ccls.)) and					
and rotat\$4)))) and 347/\$.ccls.)) and			or substrate\$1) same (stage\$4 and mov\$4		
427/\$.ccls.				1	
	L	1	1	L	·

24	13	(((((((mask\$4 or pattern\$4) and	USPAT;	2004/01/20
		(photosensitive or layer\$1 or resist\$1)	US-PGPUB;	08:48
		and (workpiece\$1 or substrate\$1)) and	EPO; JPO;	
		((mask\$4 or pattern\$4) same	DERWENT	
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		·
		fluid\$1) same (deposit\$4 or eject\$4 or		
		<pre>jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same</pre>		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) not		
		((((((mask\$4 or pattern\$4) and		
		(photosensitive or layer\$1 or resist\$1)		İ
		and (workpiece\$1 or substrate\$1)) and		
		((mask\$4 or pattern\$4) same		ļ
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
1		(support\$4 or align\$4 or stage\$4 or mov\$4		
		or rotat\$4))) and ((ink\$1 or liquid\$1 or		
		fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and		
		((mask\$4 or pattern\$4) same		
		(photosensitive or layer\$1 or resist\$1))		
		and ((workpiece\$1 or substrate\$1) same		
		(stage\$4 and mov\$4 and rotat\$4))) and		
		((mask\$4 or pattern\$4) same (negative		
		with (photosensitive or layer\$1 or		
		resist\$1))) and ((workpiece\$1 or		
		substrate\$1) same (stage\$4 and mov\$4 and		1
		rotat\$4)))) not ((((((mask\$4 or		
	:	pattern\$4) and (photosensitive or layer\$1		1.0
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or		
		pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not (((((mask\$4 or		
		pattern\$4) and (photosensitive or layer\$1		
		or resist\$1) and (workpiece\$1 or		
		substrate\$1)) and ((mask\$4 or pattern\$4)		
		same (photosensitive or layer\$1 or		
		resist\$1)) and ((workpiece\$1 or		
		substrate\$1) same (support\$4 or align\$4		
		or stage\$4 or mov\$4 or rotat\$4))) and		
		((ink\$1 or liquid\$1 or fluid\$1) same		
		(deposit\$4 or eject\$4 or jet\$4 or drop\$4		
		or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or		
		layer\$1 or resist\$1)) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4))) and ((mask\$4 or pattern\$4)		
		same (negative with (photosensitive or		
		layer\$1 or resist\$1))) and ((workpiece\$1		
		or substrate\$1) same (stage\$4 and mov\$4		
		and rotat\$4)))) and 347/\$.ccls.)) and		
	<u></u>	250/\$.ccls.	L	l